

Attorney's Docket No.: 05542-459003 / 5353C1/CMP

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Wallace Tang
Serial No. : 09/134,147
Filed : August 14, 1998
Title : IN-SITU REAL-TIME MONITORING TECHNIQUE AND APPARATUS FOR
DETECTION OF THIN FILMS DURING CHEMICAL/MECHANICAL
POLISHING PLANARIZATION

Art Unit : 1763
Examiner : Trung Dang

Commissioner for Patents
Washington, D.C. 20231

PRELIMINARY AMENDMENT

Prior to examination, please amend the application as follows:

In the claims:

Cancel claims 1-10 and 20-31 without prejudice.

11. (Amended) A chemical mechanical polisher for planarizing a film on one side of a substrate having two sides comprising at least one light source that transmits light toward the substrate from the side of the substrate with the film to illuminate at least one section on the film and create at least one reflected light signal that is received by at least one device that monitors a dimensional change based on the reflected light signal.

12. The polisher as claimed in claim 11 wherein the at least one device is positioned on the same side of the substrate as the light source.

13. The polisher as claimed in claim 11 wherein each monitored section is minimized in size to remove signal problems.

CERTIFICATE OF MAILING BY FIRST CLASS MAIL

I hereby certify under 37CFR §1.8(a) that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated below and is addressed to the Commissioner for Patents, Washington, D.C. 20231.

12-4-03
Date of Deposit
Signature